

TSMC-00-932



February 18, 2004

To: Commissioner for Patents  
P.O.Box 1450  
Alexandria, VA 22313-1450

Fr: George O. Saile, Reg. No. 19,572  
28 Davis Avenue  
Poughkeepsie, N.Y. 12603

Subject: | Serial No. 10/724,784 12/01/03 |  
May-Ho Ko  
FLASH PROCESS FOR STACKING POLY  
ETCHING  
| \_\_\_\_\_ |

#### INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.

The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56.

#### CERTIFICATE OF MAILING

I hereby certify that this correspondence is being  
deposited with the United States Postal Service as first class  
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P.O. Box 1450, Alexandria, VA 22313-1450, on February 23, 2004.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

Stephen B. Ackerman 2/23/04

U.S. Patent 6,165,375 to Yang et al., "Plasma Etching Method," discloses a flash step in an etch process.

U.S. Patent 6,165,861 to Liu et al., "Integrated Circuit Polysilicon Resistor Having a Silicide Extension to Achieve 100% Metal Shielding from Hydrogen Intrusion," discloses a method for a mixed mode product.

The following two U.S. Patents discloses processes for mixed mode products using poly etches:

- 1) U.S. Patent 6,103,622 to Huang, "Silicide Process for Mixed Mode Product with Dual Layer Capacitor and Polysilicon Resistor which is Protected with a Capacitor Protective Oxide During Silicidation of FET Device."
- 2) U.S. Patent 6,103,621 to Huang, "Silicide Process for Mixed Mode Product with Dual Layer Capacitor which is Protected by a Capacitor Protective Oxide During Silicidation of FET Device."

Sincerely,



Stephen B. Ackerman,  
Reg. No. 37761

Form PTO-1449

## INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(Use several sheets if necessary)

Doctor Number (Specimen)

TSMC-00-932

Application Number

10 | 724, 784

Logitcan!

May - Ho Ko

Filing Date

12/01/63

Group Art Unit

## U. S. PATENT DOCUMENTS

[illegible]

## FOREIGN PATENT DOCUMENTS

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Portion(s) Pages, Etc.)

[illegible]

ОДНАКО

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant